

PROCESS FOR FORMING POLYCRYSTALLINE SILICON LAYER BY LASER CRYSTALLIZATION

ABSTRACT OF THE DISCLOSURE

A process for forming a polycrystalline silicon layer includes the following steps. Firstly, at least one seed is formed on a substrate. Then, an amorphous silicon layer is formed on the substrate and overlies the seed. Then, the amorphous silicon layer is irradiated with a laser to melt the amorphous silicon layer. Afterward, the molten amorphous silicon layer is recrystallized to form a polycrystalline silicon layer.